

Notice of References CitedApplication/Control No.
09/787,457Applicant(s)/Patent Under
Reexamination
ADELERHOF ET AL.Examiner
Maria GuerreroArt Unit
2822

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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,486,662	11-2002	Ruigrok et al.	324/252
	B	US-6,365,948	04-2002	Kumagai et al.	257/421
	C	US-5,650,958	07-1997	Gallagher et al.	365/173
	D	US-6,544,801	04-2003	Slaughter et al.	438/3
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Blamire et al. "A new Self-Aligning Process For Whole-Wafer Tunnel Junction Fabrication", March 1989, IEEE, pages 1123-1126.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.